

SU-8 3050 – run sheet

Kayaku MicroChem / MicroChem Corp.

nanyte.com/photoresists/su-8-3050 · last updated 2026-07-26

Thickness: 44.3–101.3 μm

Softbake: 95 °C · hotplate

Exposure dose – dose by film thickness

Film thickness	Dose
4–10 μm	100–200 mJ/cm^2
8–15 μm	125–200 mJ/cm^2
20–50 μm	150–250 mJ/cm^2
30–80 μm	150–250 mJ/cm^2
40–100 μm	150–250 mJ/cm^2

Post-exposure bake: 95 °C · 3–5 min

Develop: Developer SU-8 Developer (MicroChem's proprietary solvent-based developer); ethyl lactate and diacetone alcohol are also stated to work · Rinse Spray/wash with fresh SU-8 developer for ~10 s, then a second spray/wash with isopropyl alcohol (IPA) for ~10 s, then air/nitrogen dry with filtered pressurized gas. A white film appearing during the IPA rinse indicates under-development -- immerse or spray with more SU-8 developer and repeat the rinse. Ultrasonic or megasonic bath agitation is recommended for developing out vias/holes in high-aspect-ratio structures.

Hardbake: 150–200 °C